

SAMPLE PREPARATION **TOOLS FOR**

Failure Analysis - Quality Assurance Forensics - Detecting Counterfeit Reverse Engineering







New 2023 Full Stainless Steel & TFE

DC has published more than 14 years ago the way to use Acids or Plasma for Cu wires package without any damage



Comparative Study on Decapsulation for Copper and Silver Wire-Bonded Devices Francois KERISIT - Digit Concept

"iSP DCap™

Vacuum Plasma DCapsulation

SP RIE™



info@digit-concept.com

ESREF2011 ... Plasma

New front side access approach for Low-k dielectric/Cu technologies in plastic package.

iSP DCap™

Amandine AUBERT - STM **VACUUM PLASMA Dcapsulation** Cu / BCB With iSP DCap™



Ontical view of the failed componen after resin removal with Vacuum iSP_DCap™ O2 Only. The red circle corresponds to the defect area

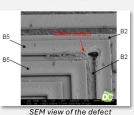


Figure 3b. SEM micrograph

ISTFA2011 ... Acids

New method for decapsulation of Copper wire devices using LASER and sub ambient temperature chemical etch.

iSAcids™

Pascal GOUNET - STM Matthew LEFEVRE - Digit Concept

ASER + ACIDS DCapsulation ™ With سُلَا SLaser ما Acids الكاني With



LASER pre-DCap 2.5W 10KHz 300mm/s 10ns

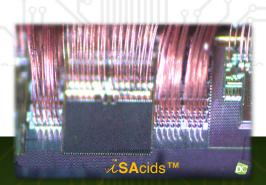


showing state of die bonds and wires after decapsulation at 15°C



FA Solutions and HighTech Equipment

*x*iSLaser™ 4 Ways of IC DCap



"∴MIPlasma™

Mill TM

SPECIAL CAM WORKSHOP

Release 33 YEARS

SESAME**ACID™**

SESAMELASER™

SESAME**PLASMA™**

SESAME**PLASER™**

SESAME**THERMAL™**

SESAME**MECHANICAL™**

SESAMEDUOLASER™

SESAME**ENDPT™**

A GREEN WORLD WITH DC - LESS ACID - LESS CF4 - AND ALL FOR YOUR FUTURE IC PACKAGES



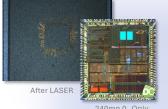
SAcids™



*≅MIP*lasma II™ The first one ... and the best one today ... You will now understand why It's time to disclose some secrets you can have with the 2024 Release @



Welcome in the future ... it's now !!!



Fully automatic: choose your recipe and start during the day or the night. That's all !!!

- Atmospheric Plasma DCapsulation O₂ only or all other gases
- > Au Al Cu Ag wires SiC, GaN Compatible
 - > Automatic alignment by LASER during the process to have always the same distance between MIP Source and component for a better etch rate
- Adayanced Camera HR autofocus with full record of the picture during the DCapsulation. Second Large screen to see all the details.
 - Depassivation
- Ready for More-than-Moore (MTM) technologies
 - And more ...

For more information

iMIP@digit-concept.com



ZMIPlasma II XL™

World premiere *©*

... expected for long time





> IC stay in place so no need to de-solder this one (no Thermal and Mechanical Stress = Less Artefact)

> & you have all the components around for the tests after (no need to resolder).

> > Advanced measurement of the height of all components at the surface of the PCB to take care if it's possible without damage anything

No Ultrasonics damage for sensitive IC ...

Choose to remove the fillers (SiO₂) between Liquid Blow, CO₂ Blast (Patented) or Ultrasonics Bath.

> The 3 in standard @

> The new iMIP IIXL 2024 is already installed at Customer plants!

During MIP

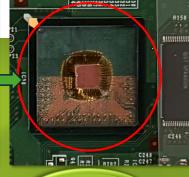
PCB 250x220mm

After MIP

and SLP500 LASER to remove EMC and conformal coating











AppleWatch™ Teardown



SiC





PATENT WO 2008/090281





Large Power

Finger Print IC **FULL RANGE** DECAPSULATOR

SESAME**ACID™** SESAME**LASER™** SESAME**THERMAL™** SESAME**MECHANICAL™**

SESAMEPLASM™ SESAME**PLASER™** SESAME**DUALASER™**

More than 250 Equipments installed in the World